CLAIMS

1. A holding apparatus for applying an electrolytic plating treatment to a planar workpiece comprising:

a rear member; and

a front member facing the rear member and having an opening part,

wherein the planar workpiece is disposed between the rear member and the front member,

the front member has a plurality of electrodes and a plurality of first insulating parts,

the plurality of electrodes and the plurality of first insulating parts cover an edge part of the planar workpiece in a width direction of the planar workpiece,

provided that an edge length of the planar workpiece in the width direction of the planar workpiece or an edge length of the opening part in a direction parallel to the width direction of the planar workpiece, whichever is smaller, is defined as 100, an edge part-covering length of the plurality of first insulating parts or the plurality of electrodes is 80 or more in the width direction of the planar workpiece within the edge length of the planar workpiece in the width direction of the planar workpiece,

wherein the front member has a second insulating part, and

the second insulating part covers each of the first insulating parts and/or each of the electrodes.

2. The holding apparatus according to claim 1,

wherein each of the first insulating parts has a projection towards the rear member.

3. The holding apparatus according to claim 2,

wherein the projection is formed across each of the first insulating parts in a width direction of each of the first insulating parts.

4. The holding apparatus according to any one of claims 1 to 3,

wherein an end of each of the electrodes contacts the planar workpiece,

the end has a curved part towards the planar workpiece, and

the curved part is formed across each of the electrodes in a width direction of each of the electrodes.

5. The holding apparatus according to claim 1,

wherein the second insulating part has a projection towards the rear member,

the projection is formed at a peripheral edge of the opening part.

6. The holding apparatus according to any one of claims 1 to 5,

wherein each of the first insulating parts contacts the edge part of the planar workpiece.

7. The holding apparatus according to any one of claims 1 to 6,

wherein each of the first insulating parts and each of the electrodes are disposed alternately along an edge of the planar workpiece.

8. The holding apparatus according to any one of claims 1 to 7,

wherein each of the first insulating parts and each of the electrodes are disposed alternately along the edge of the planar workpiece and are in contact with one another.

9. The holding apparatus according to any one of claims 1 to 8,

wherein each of the electrodes is covered with an insulating film except for a contact point of each of the electrodes with the planar workpiece.

10. A method for applying an electrolytic plating treatment to a planar workpiece with the holding apparatus according to any one of claims 1 to 9,

wherein the electrolytic plating treatment is performed with each of the electrodes in contact with a plating solution.